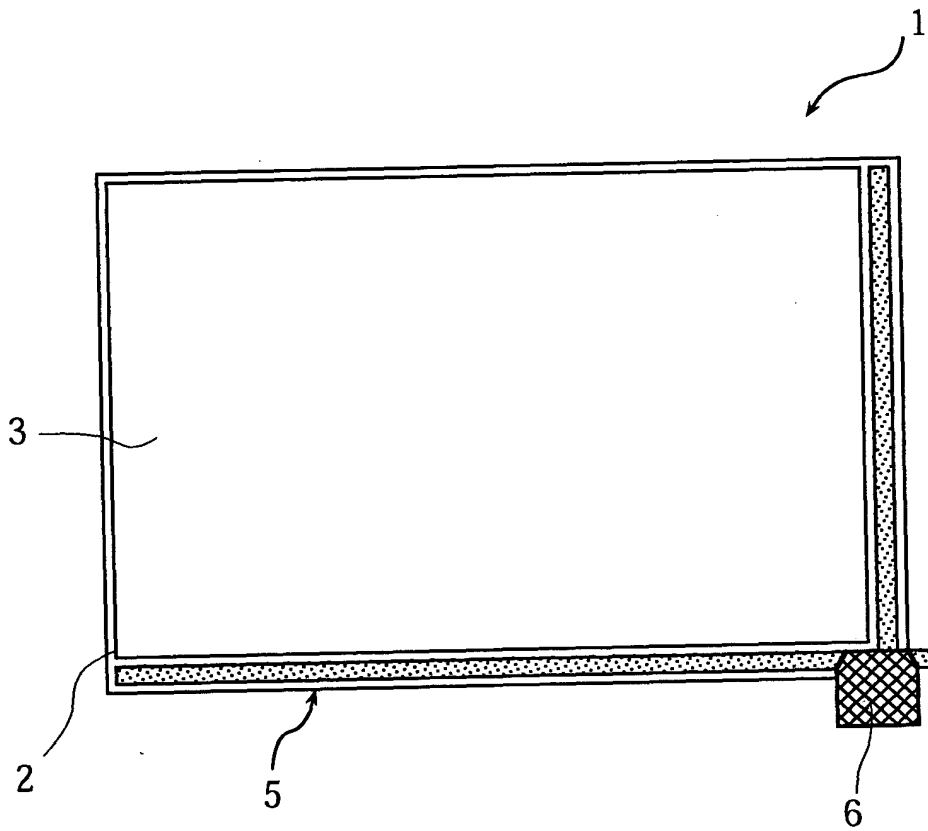


Fig. 1



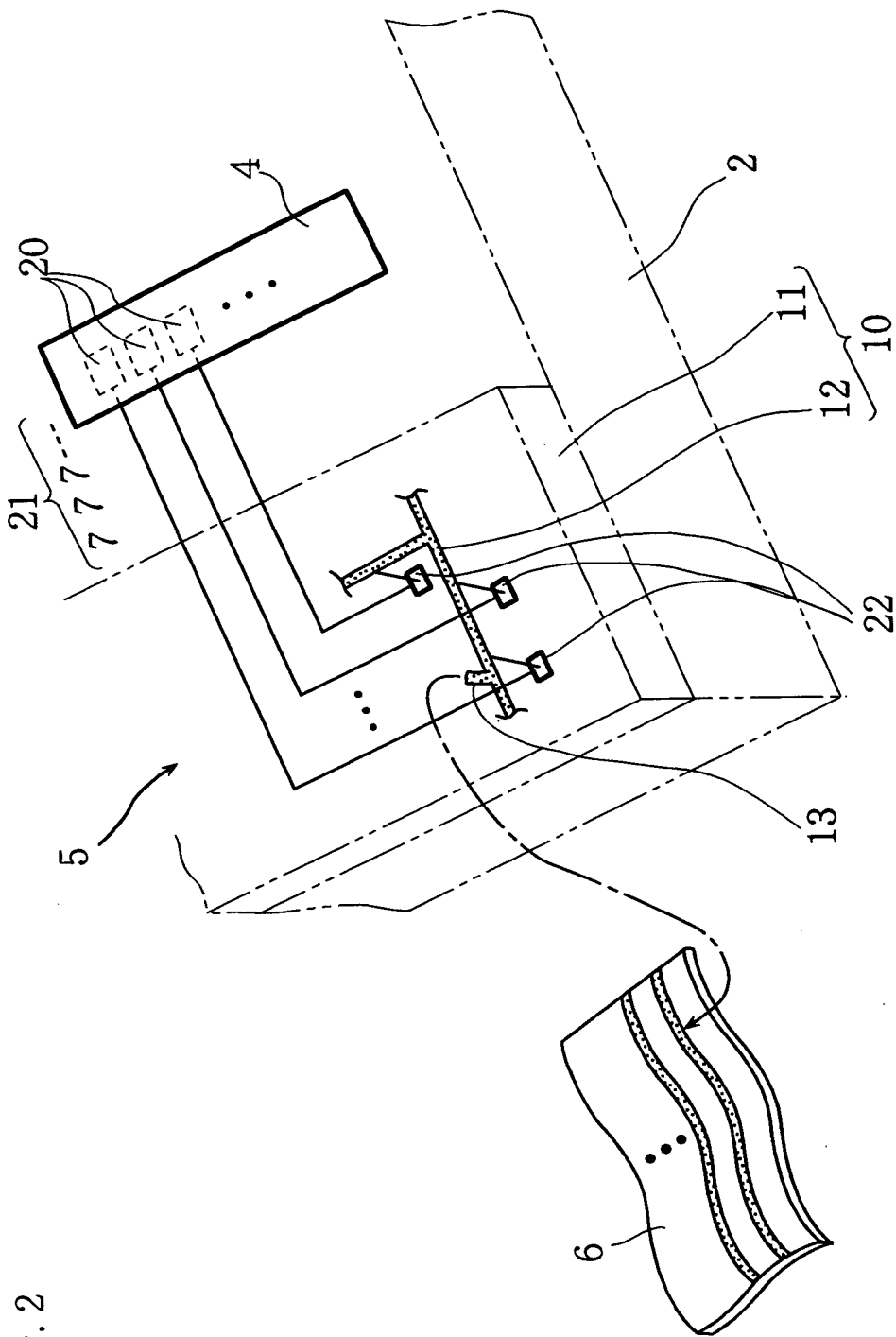


Fig. 2

Fig. 3

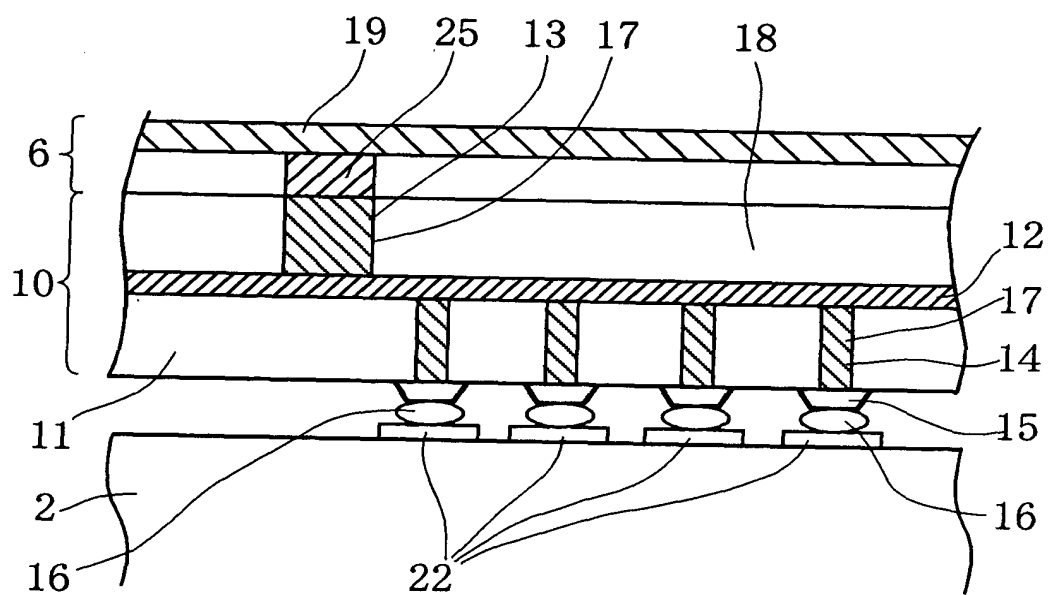


Fig. 4

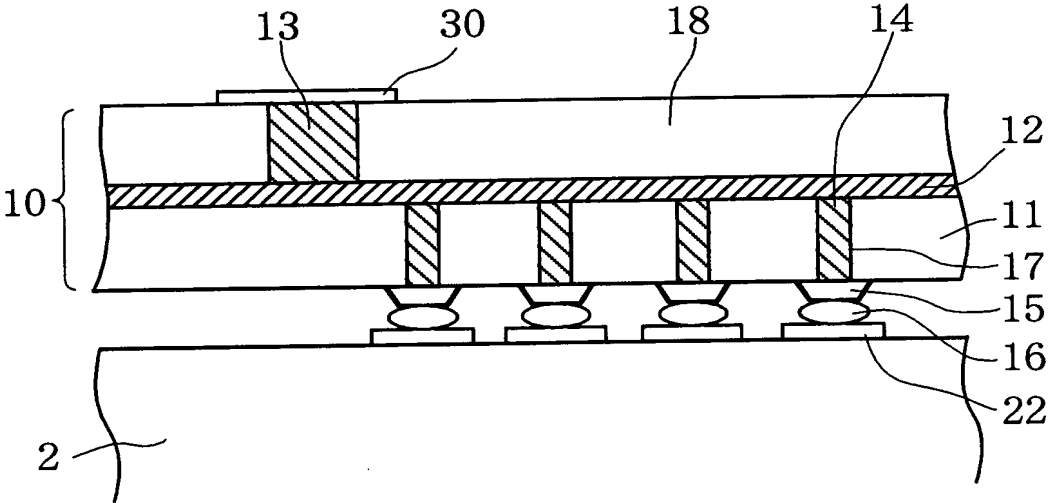


Fig. 5

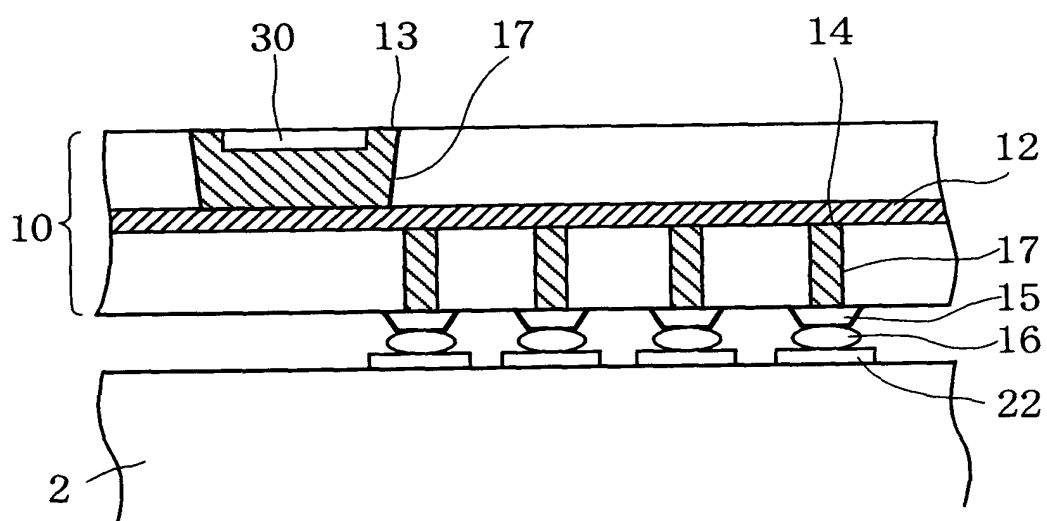


Fig. 6

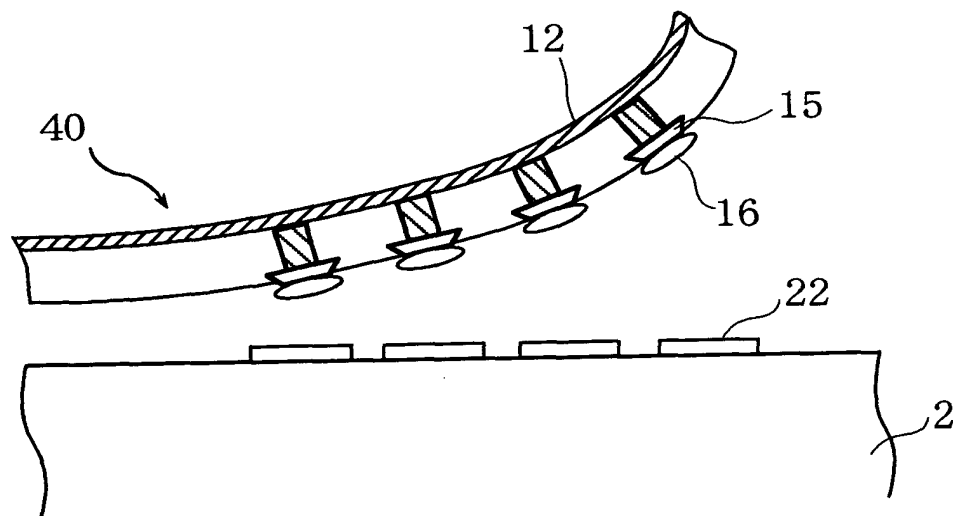


Fig. 7

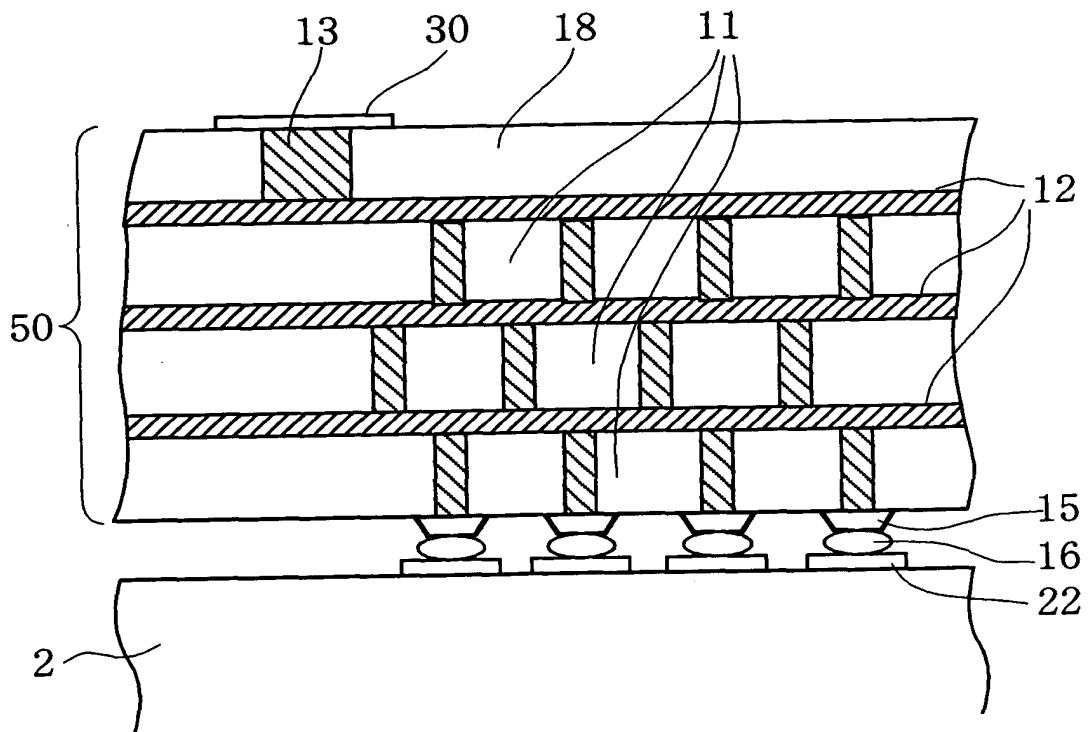


FIG. 8

Fig. 8

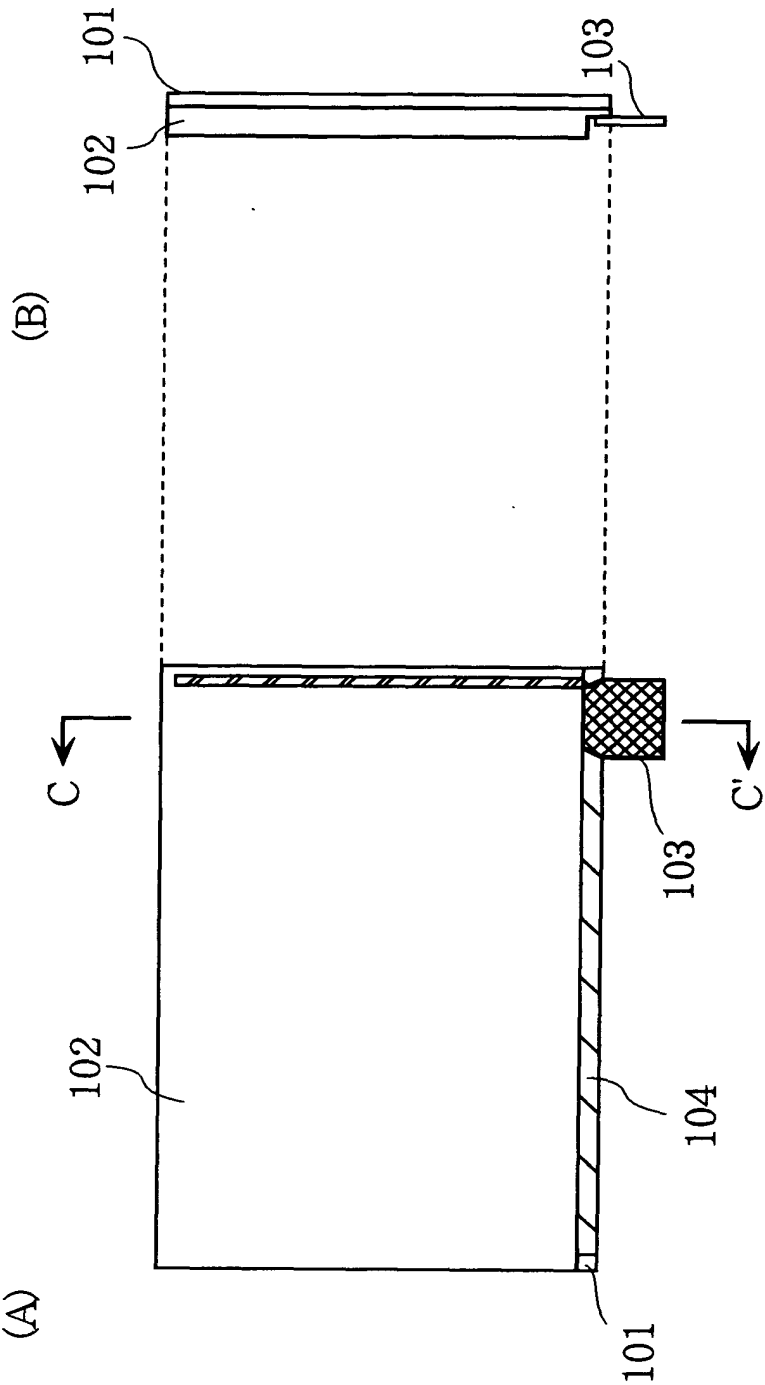
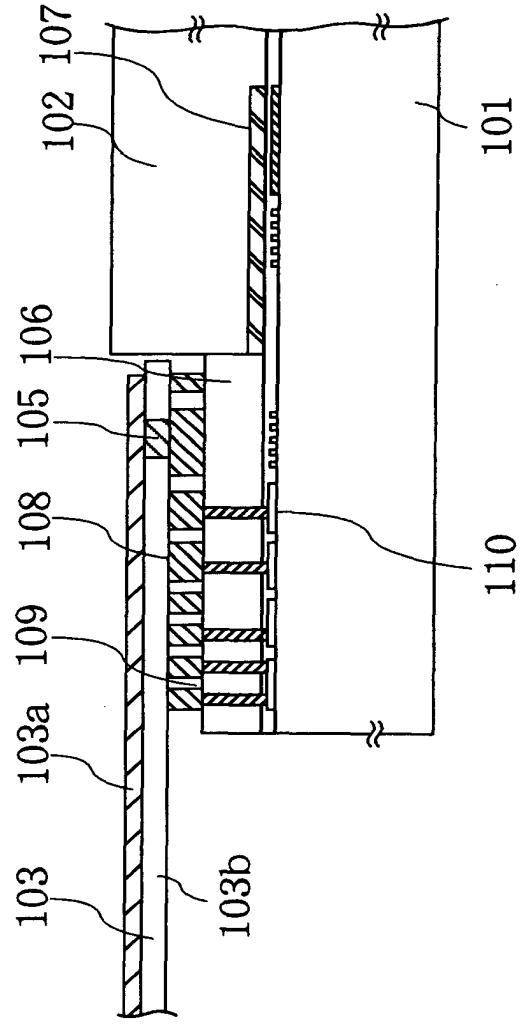


Fig. 9



(A) After The Formation of ITO

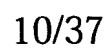
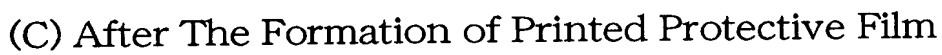
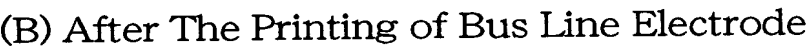
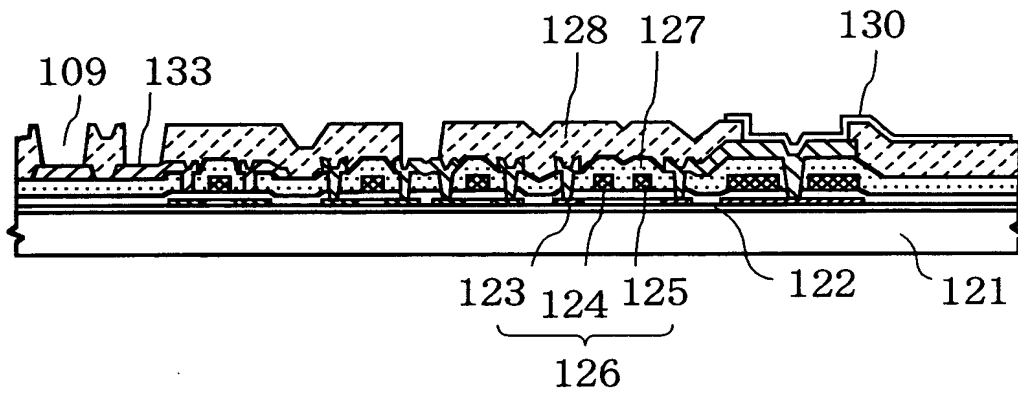
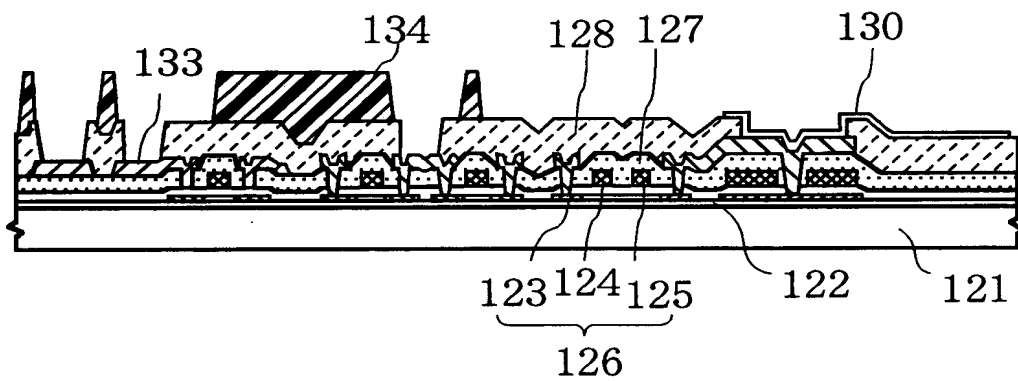


Fig. 11

(A) After The Formation of ITO



(B) After The Printing of Insulating Film



(C) After the Formation of Bus Line Electrode

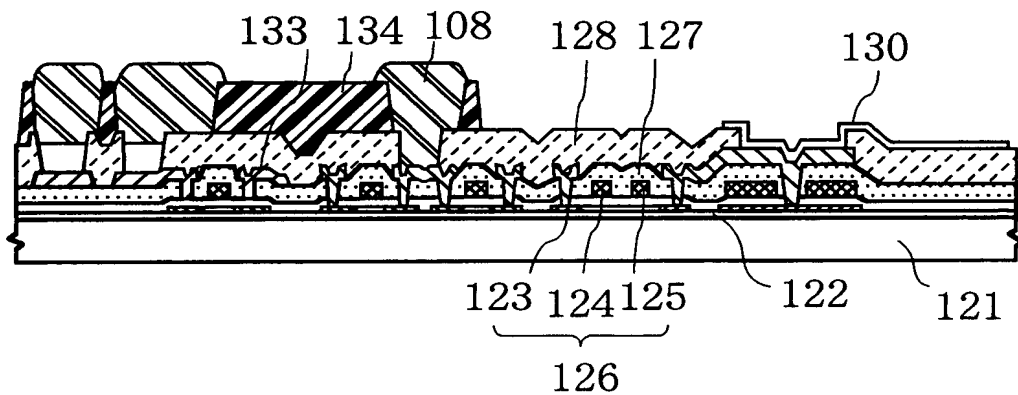
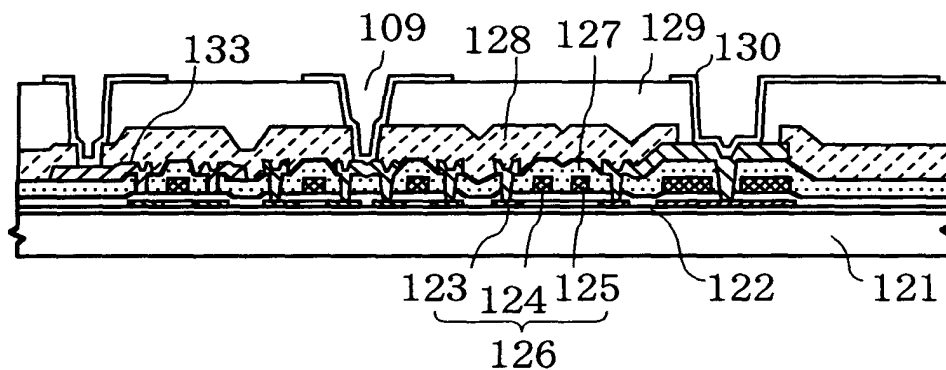
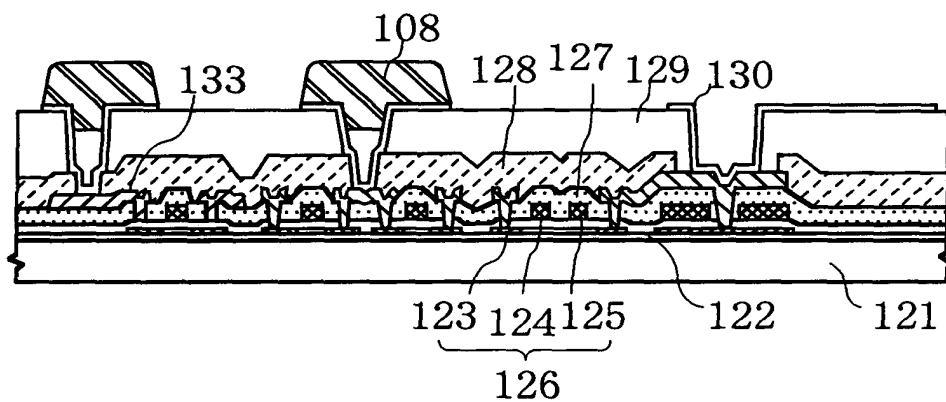


Fig. 12

(A) After The Formation of ITO



(B) After The Formation of Bus Line Electrode



(C) After The Formation of Printed Protective Film

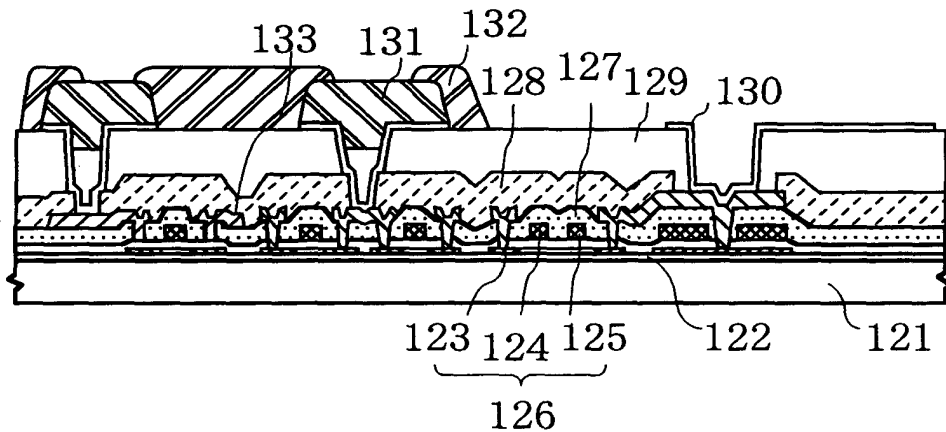
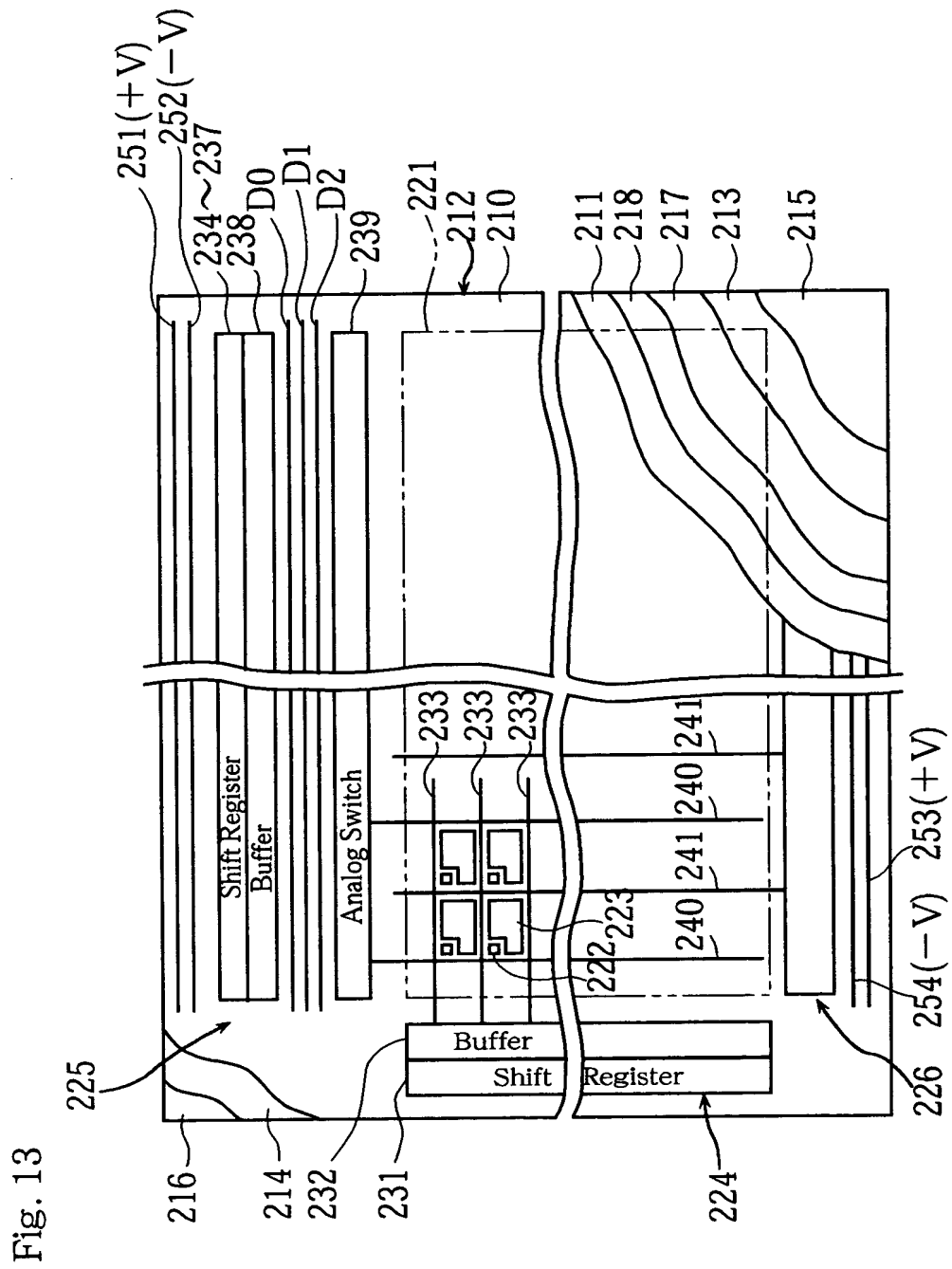


FIG. 13



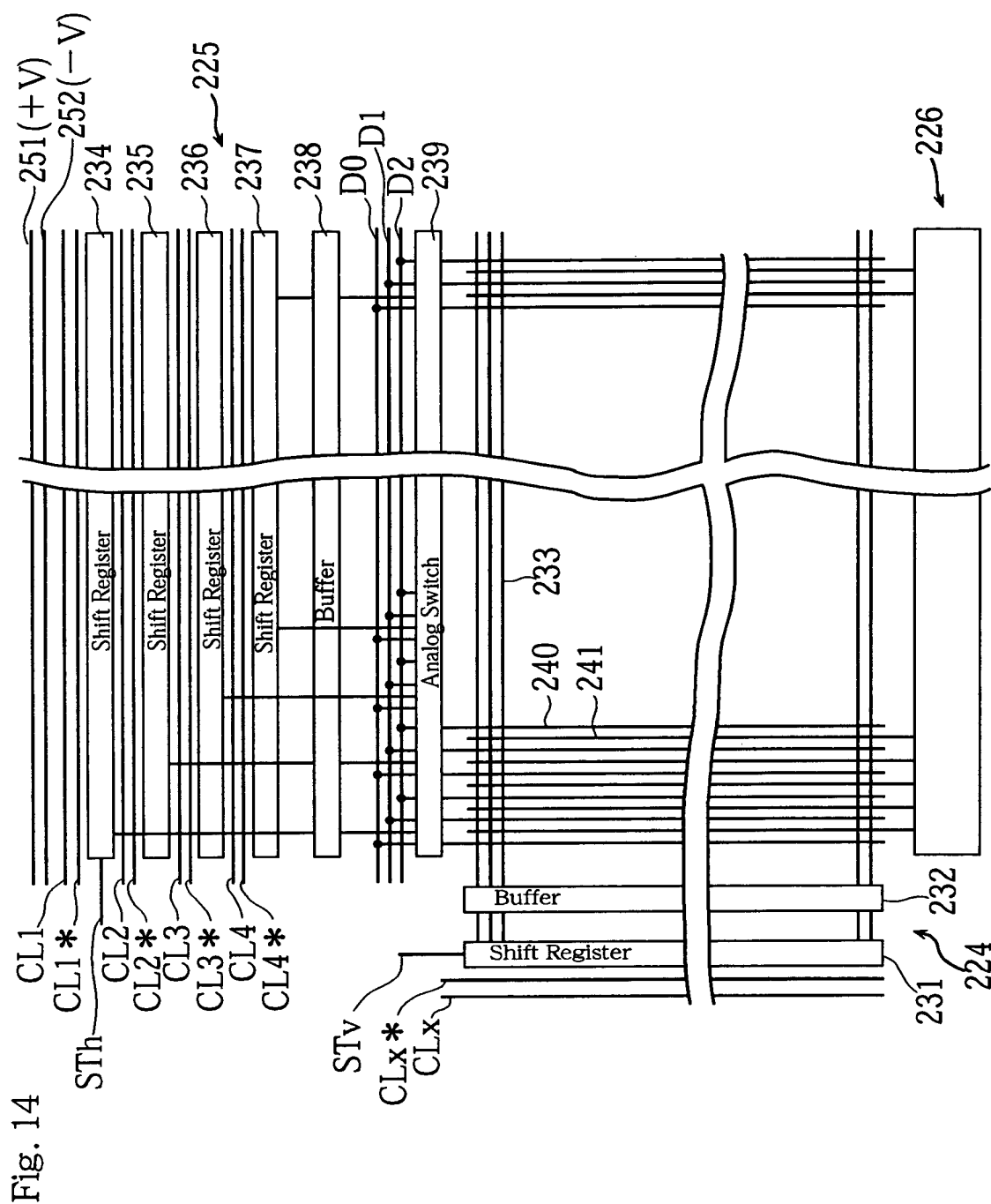


Fig. 15

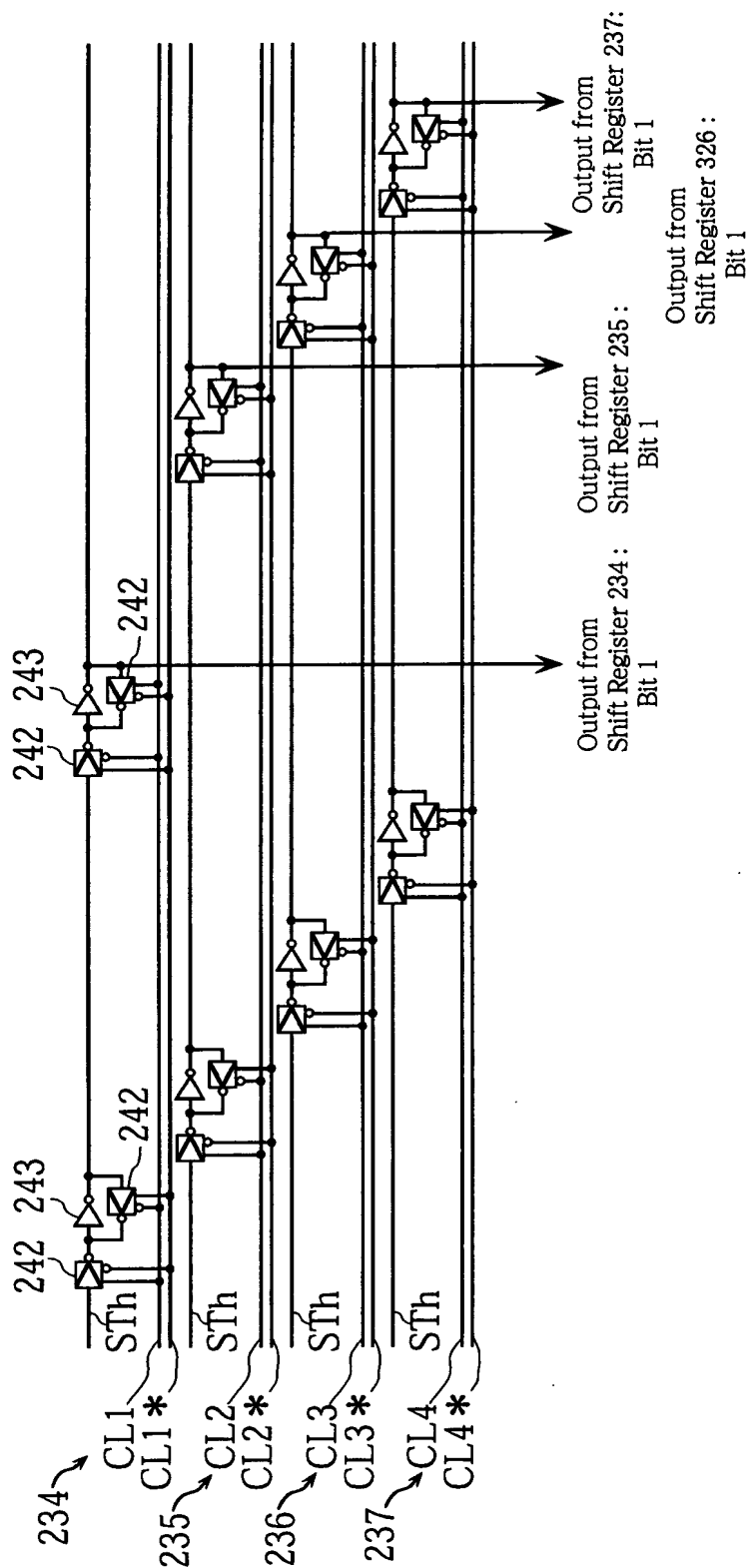


Fig. 16

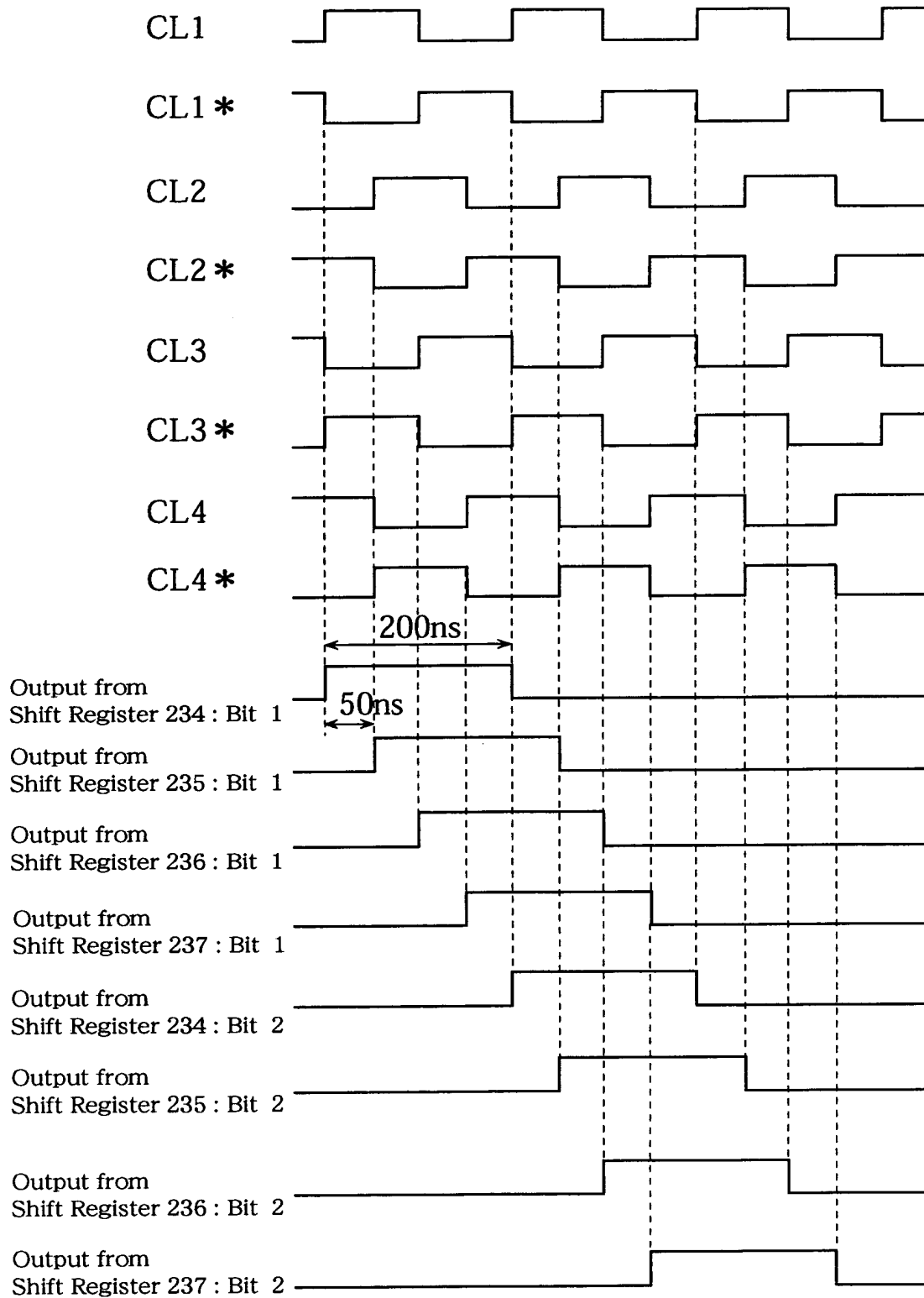


Fig. 17

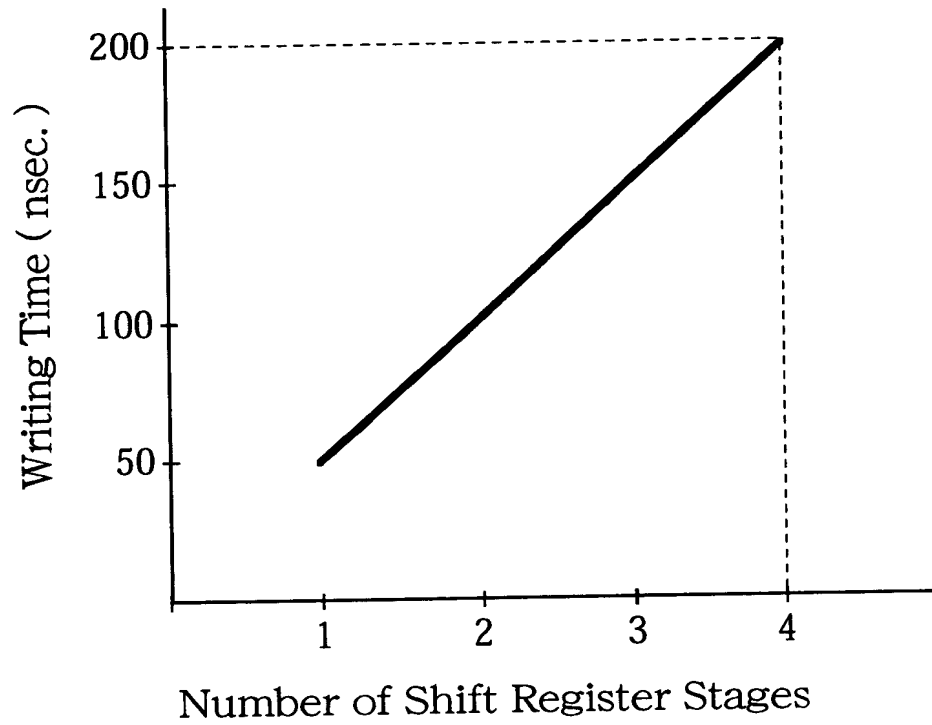


Fig. 18

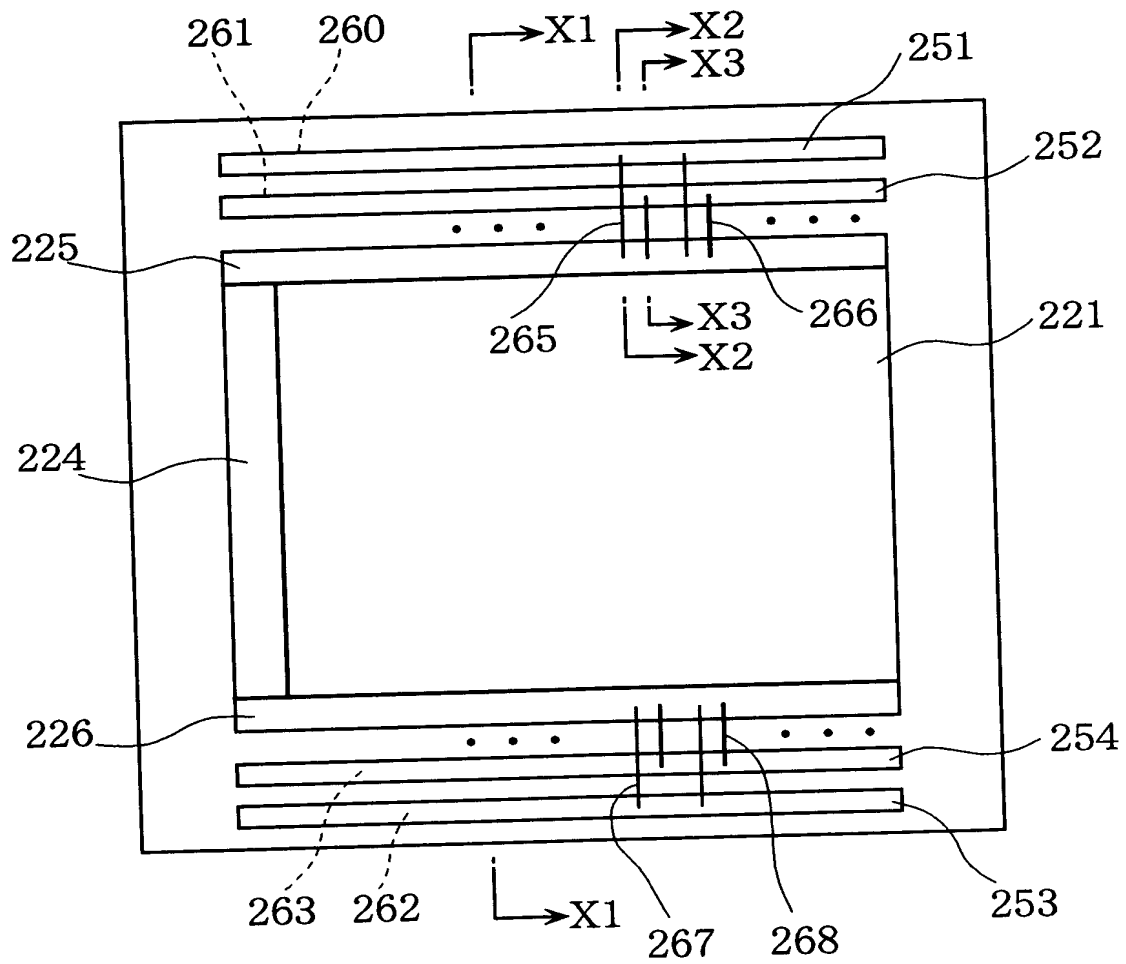


Fig. 19

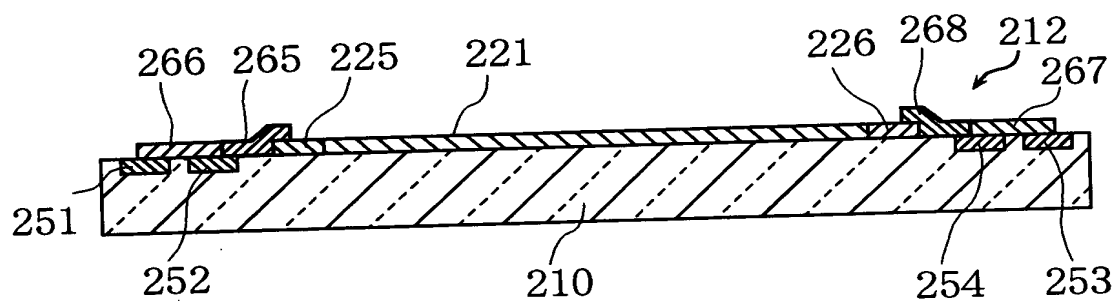


Fig. 20

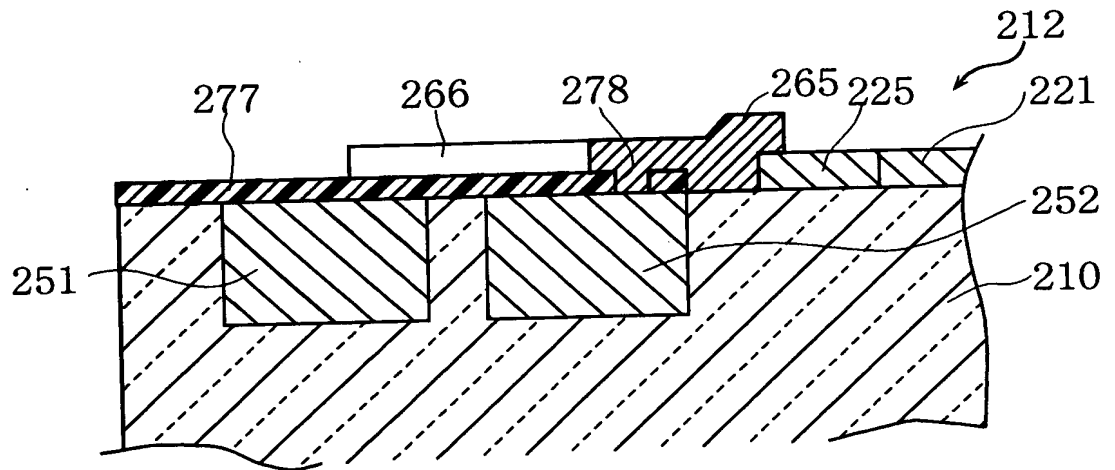


Fig. 21

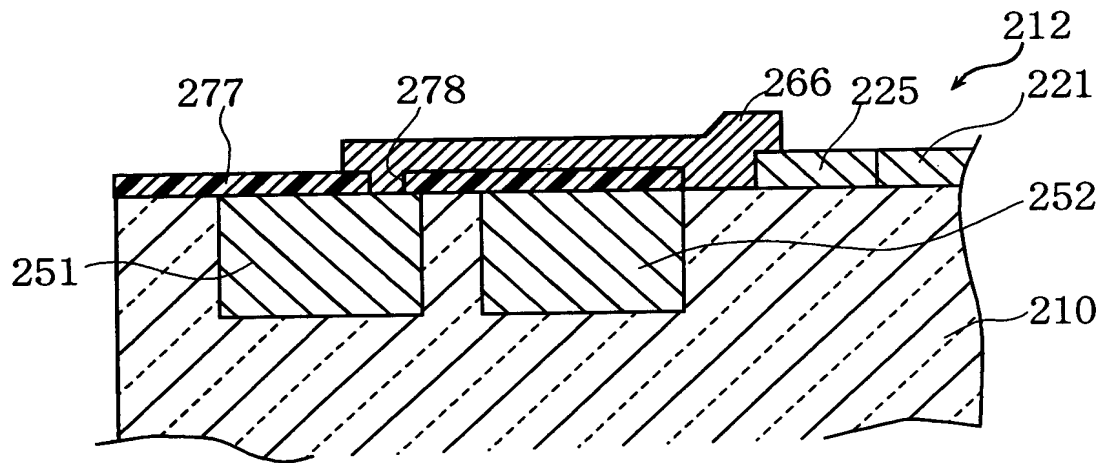


Fig. 22

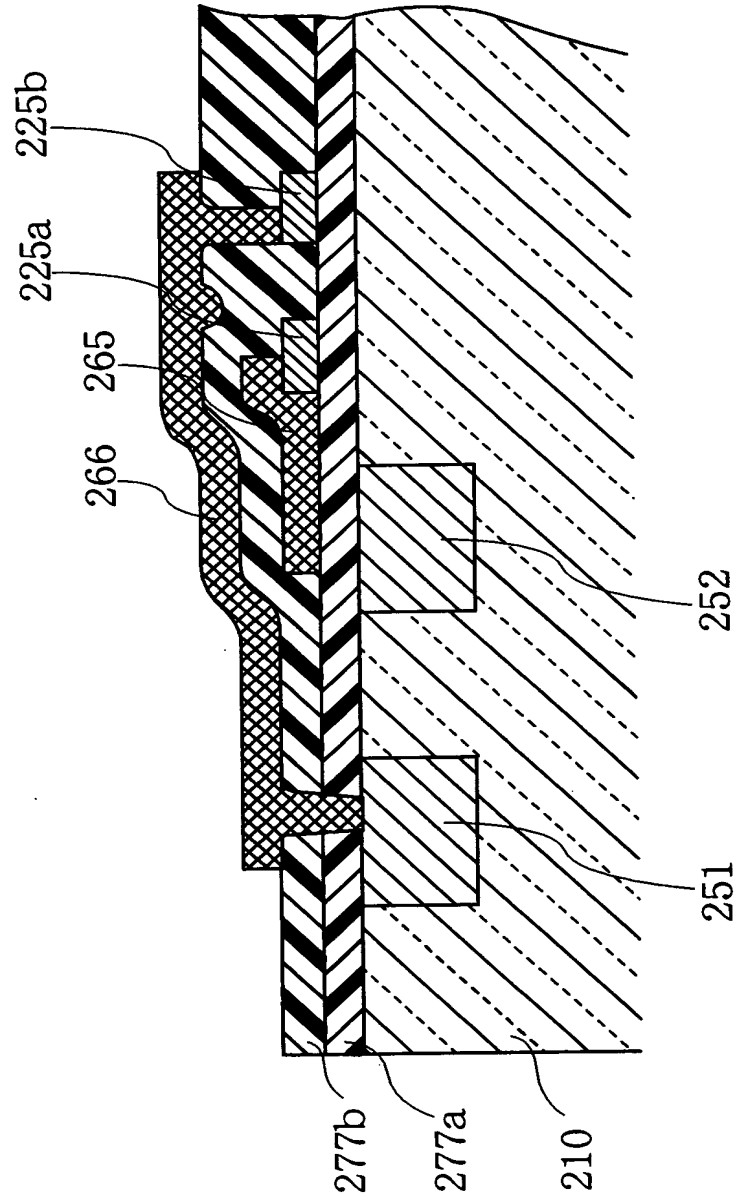


Fig. 23

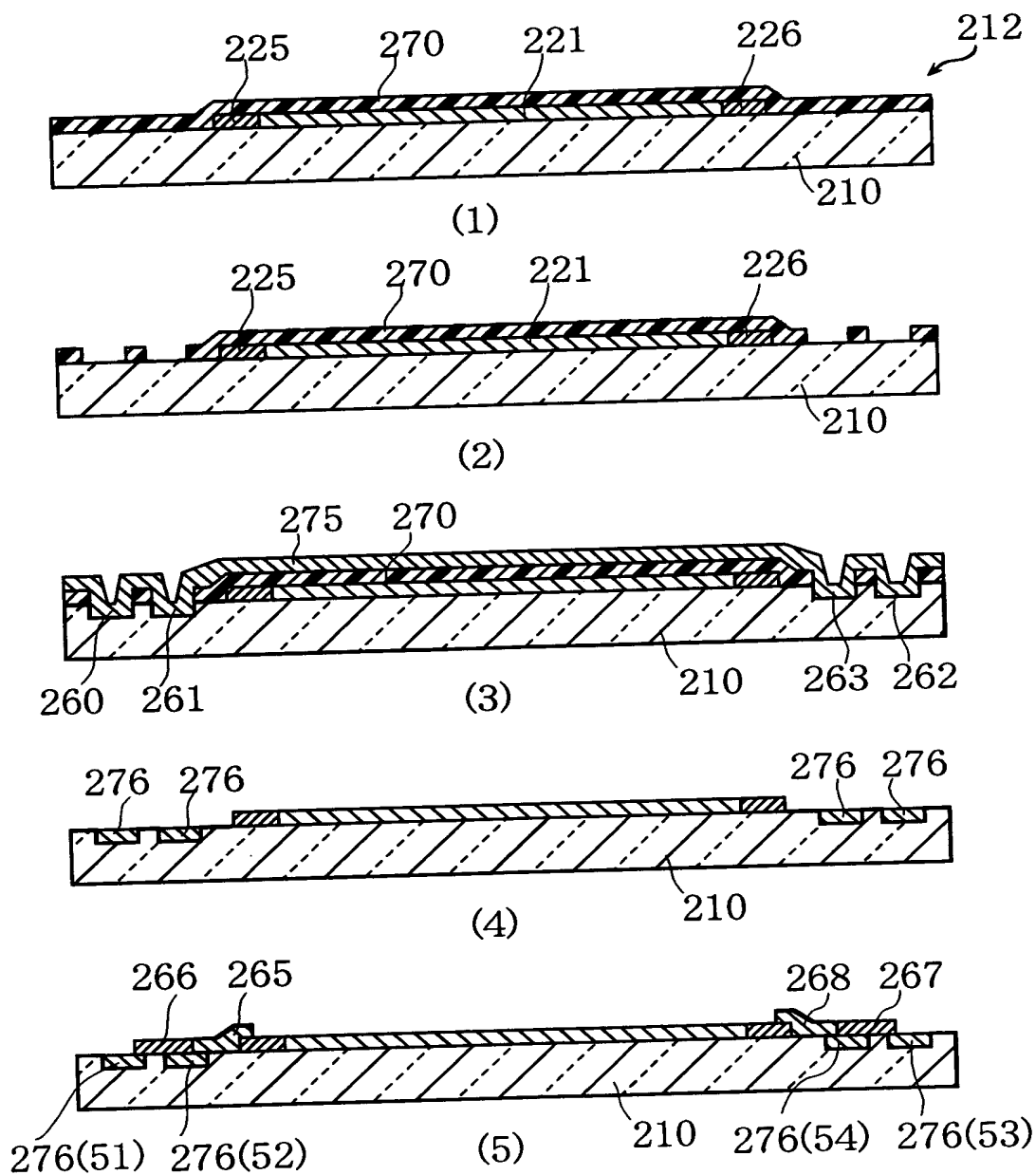


Fig. 24

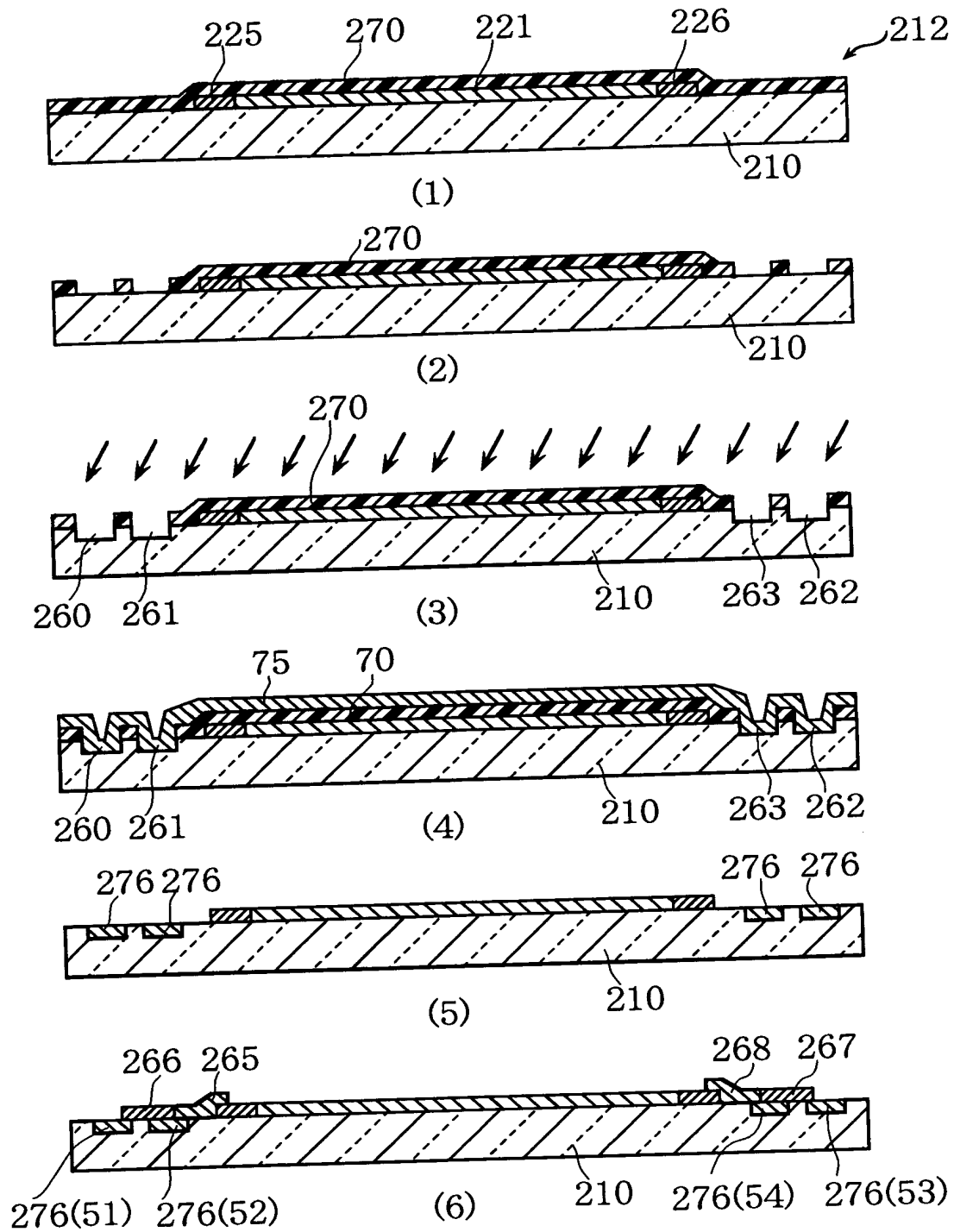


Fig. 25

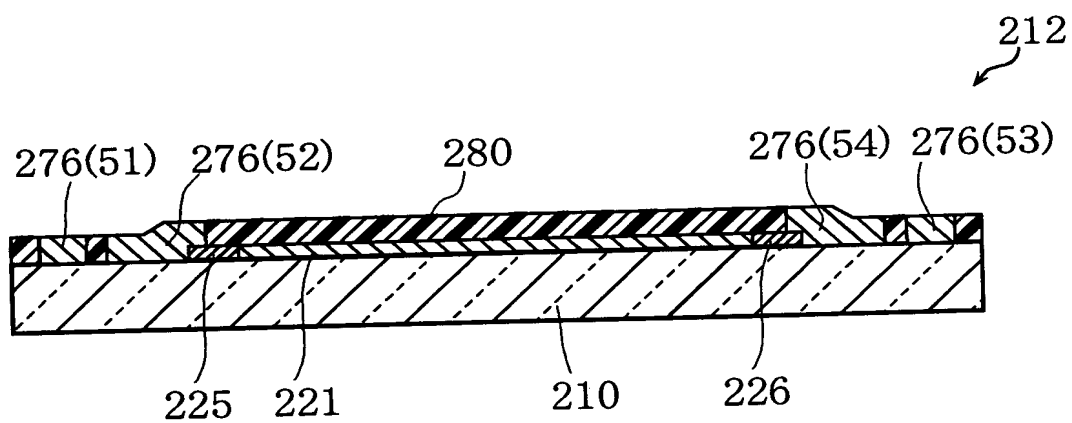


Fig. 26

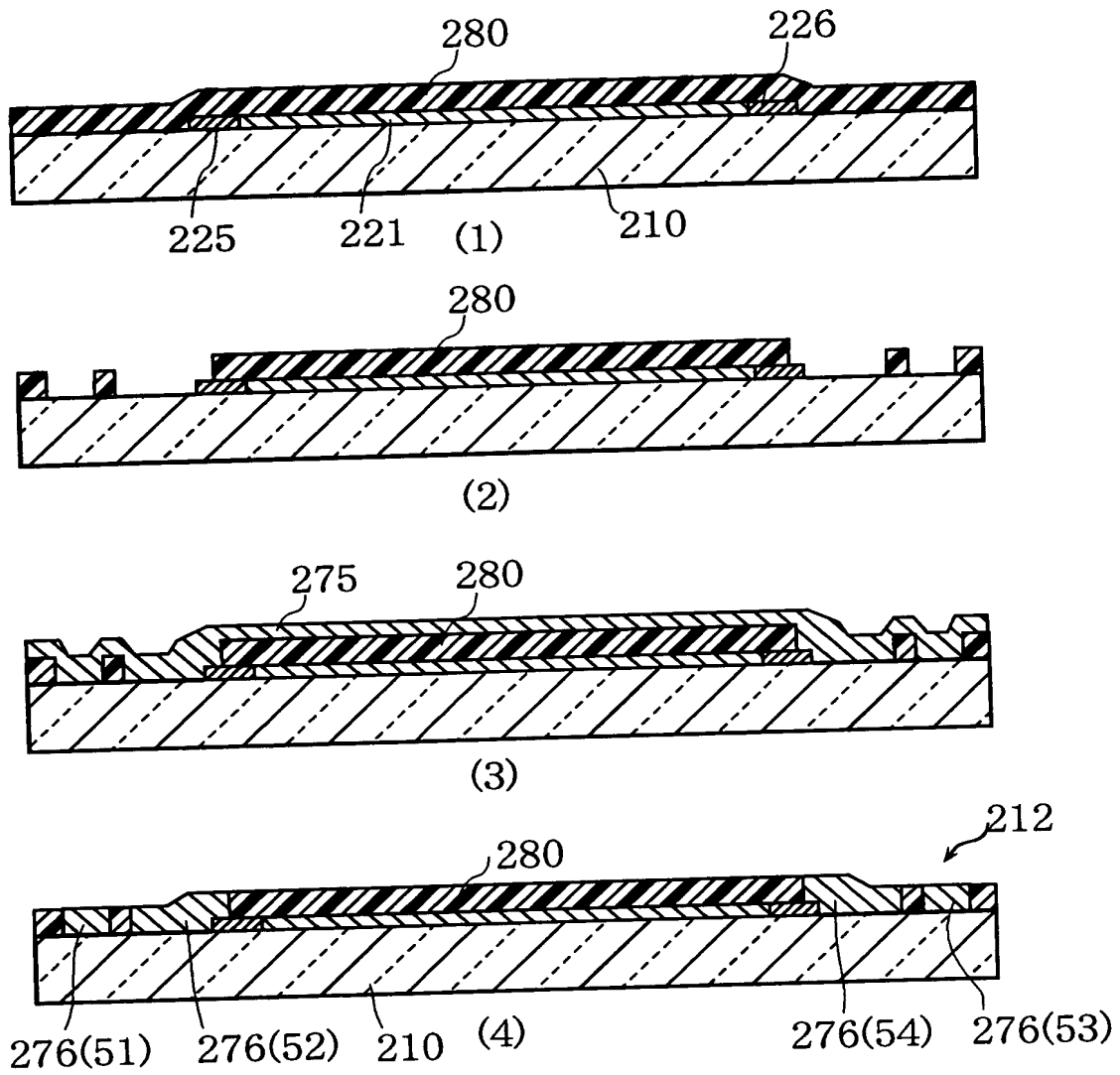


Fig. 27

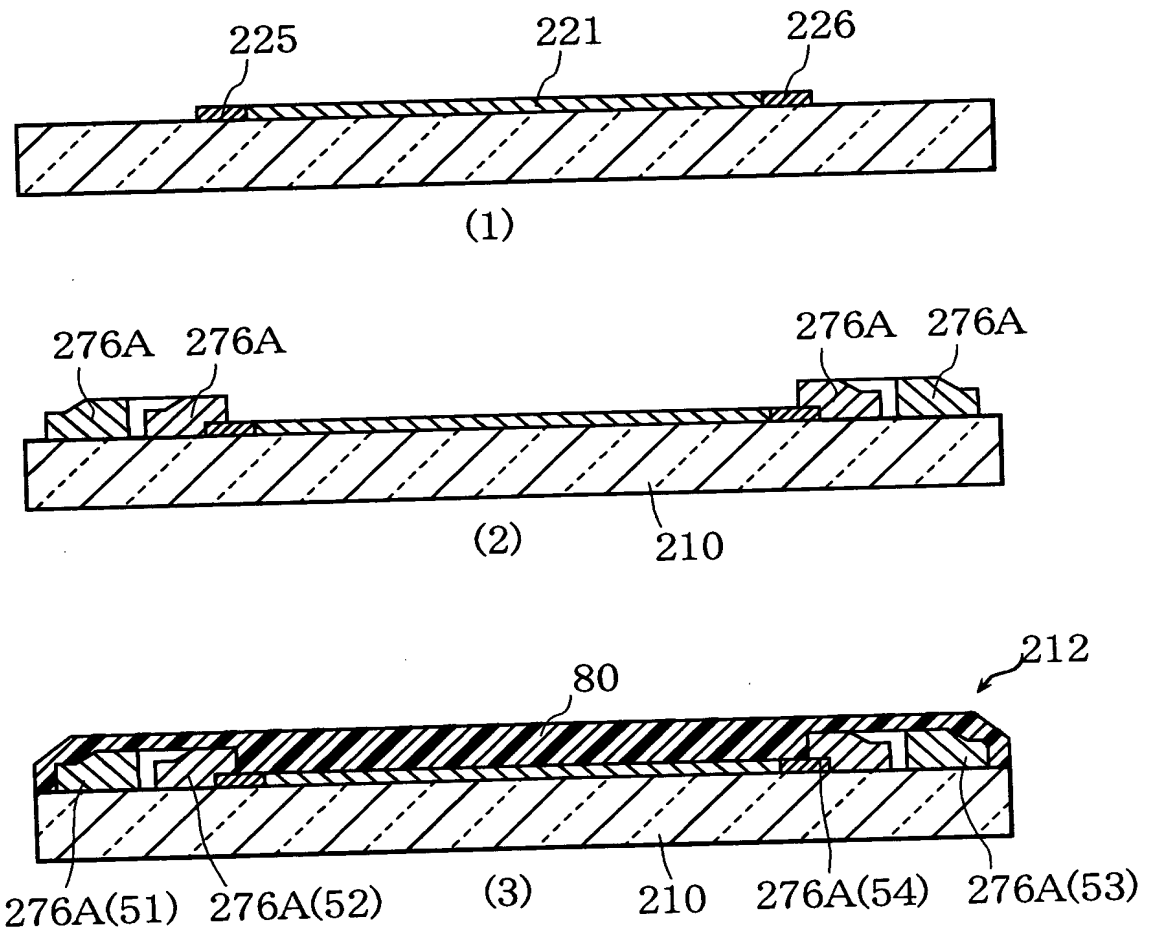


Fig. 28

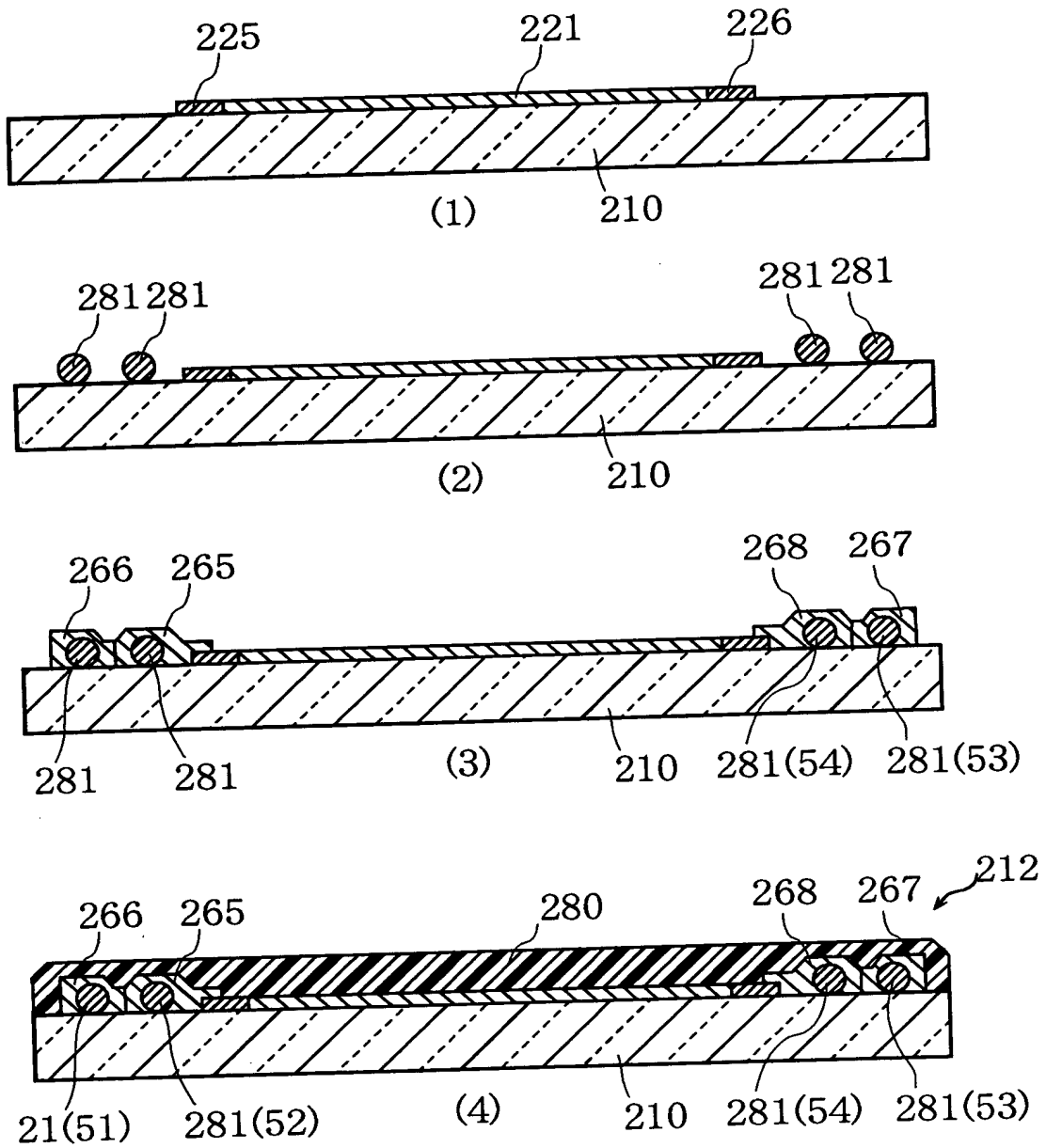


Fig. 29

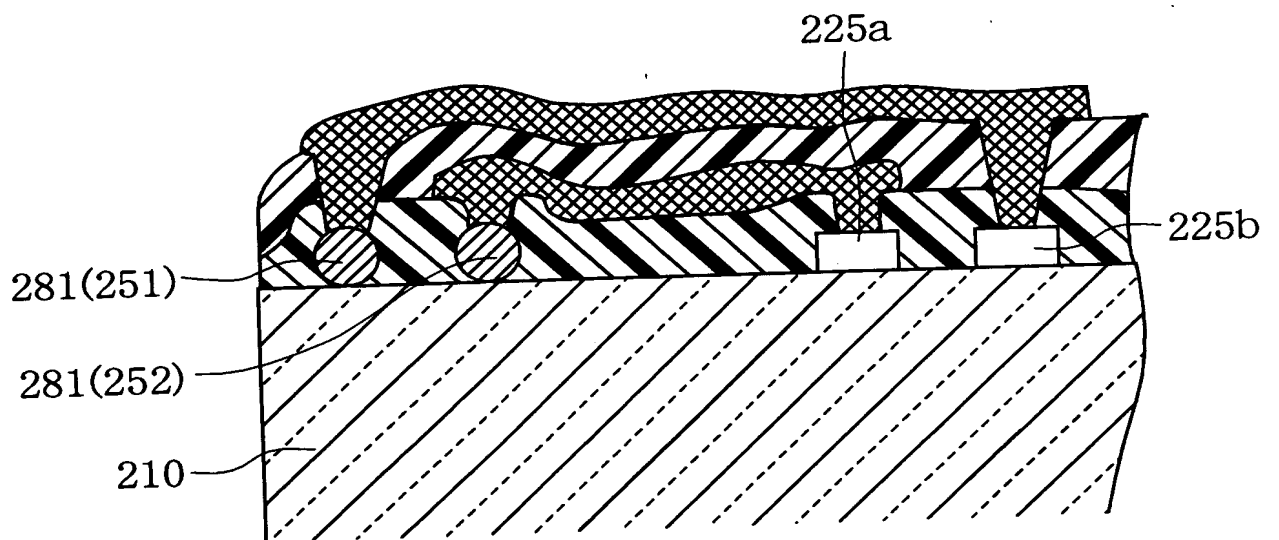


Fig. 30

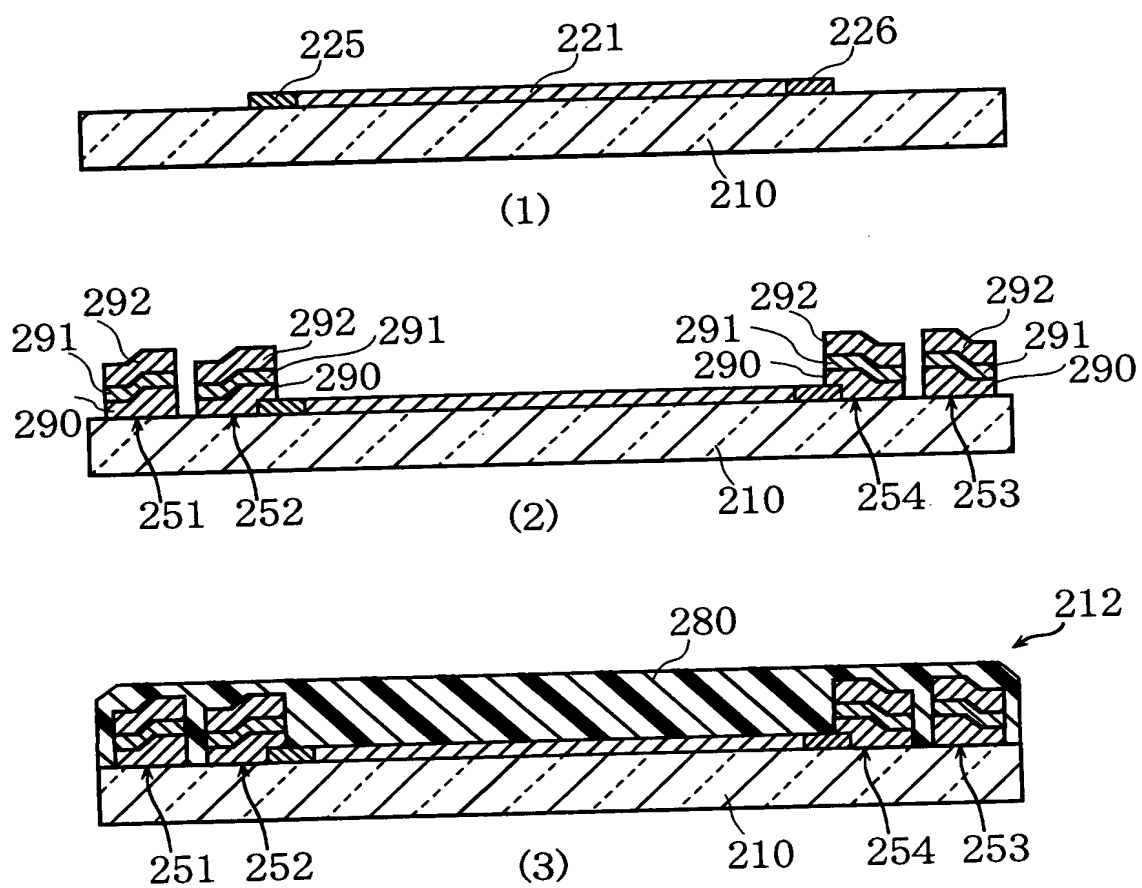


Fig. 31

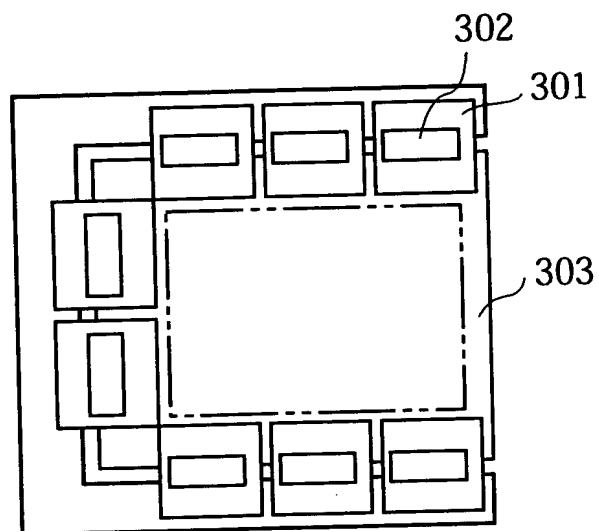


Fig. 32

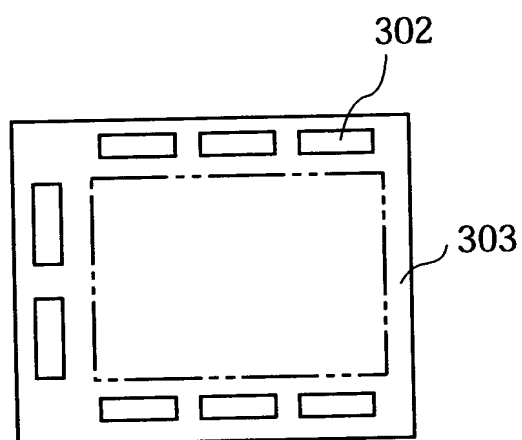


Fig. 33

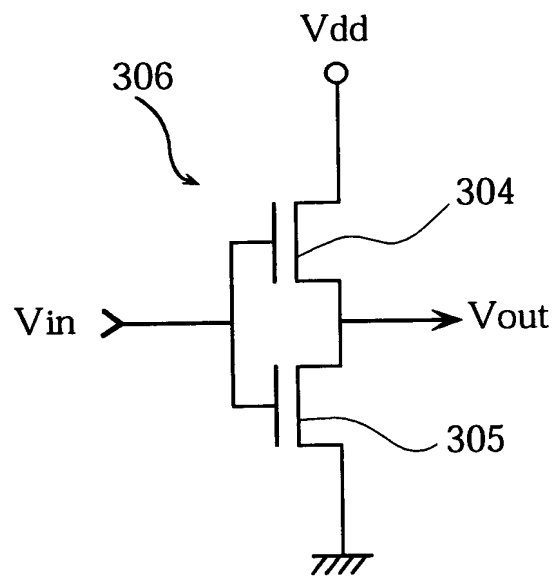
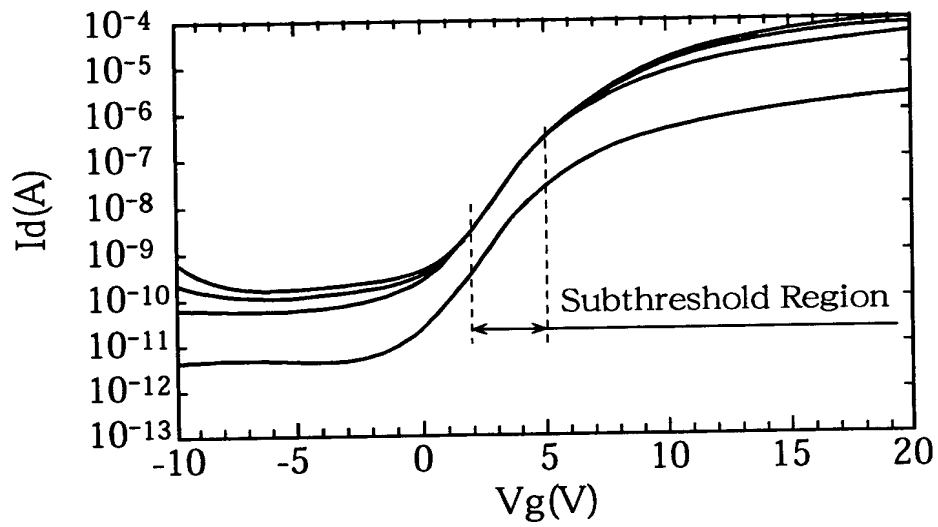


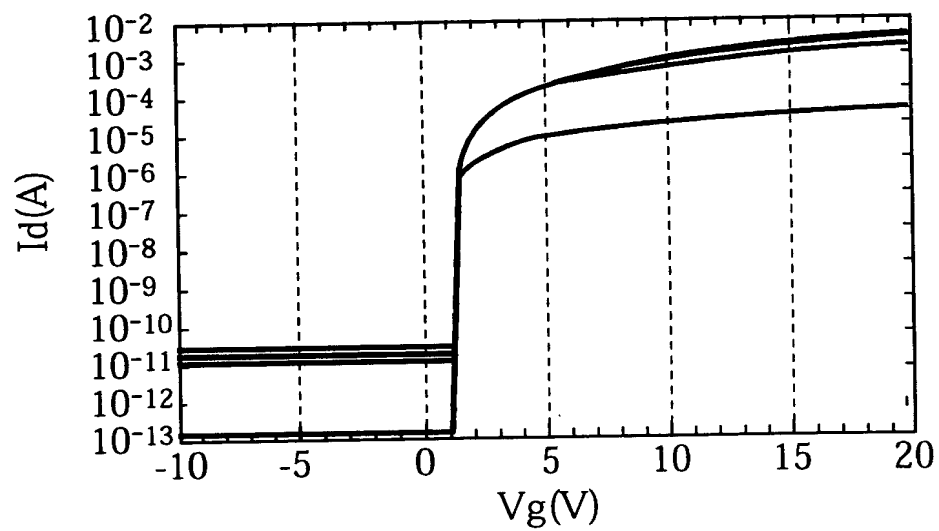
Fig. 34

(a)



Characteristics of Polysilicon TFT

(b)



Characteristics of Mos-Tr (Crystalline Silicon)

Fig. 35

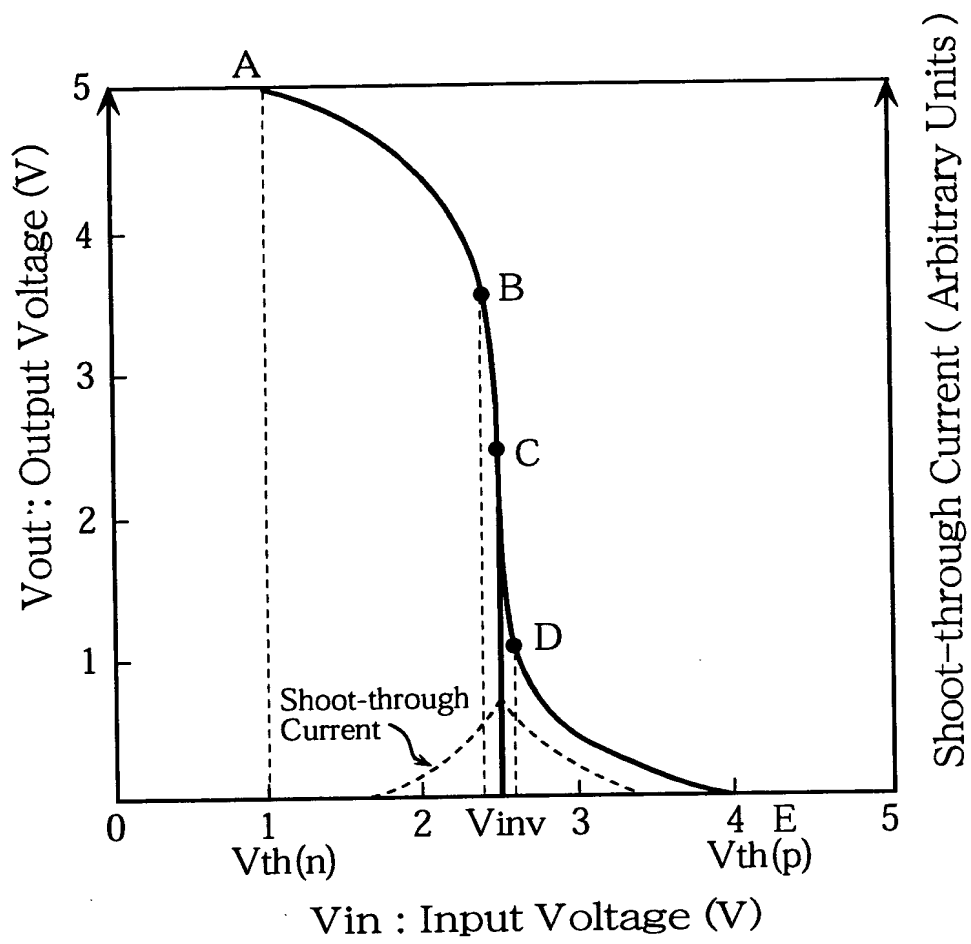


Fig. 36

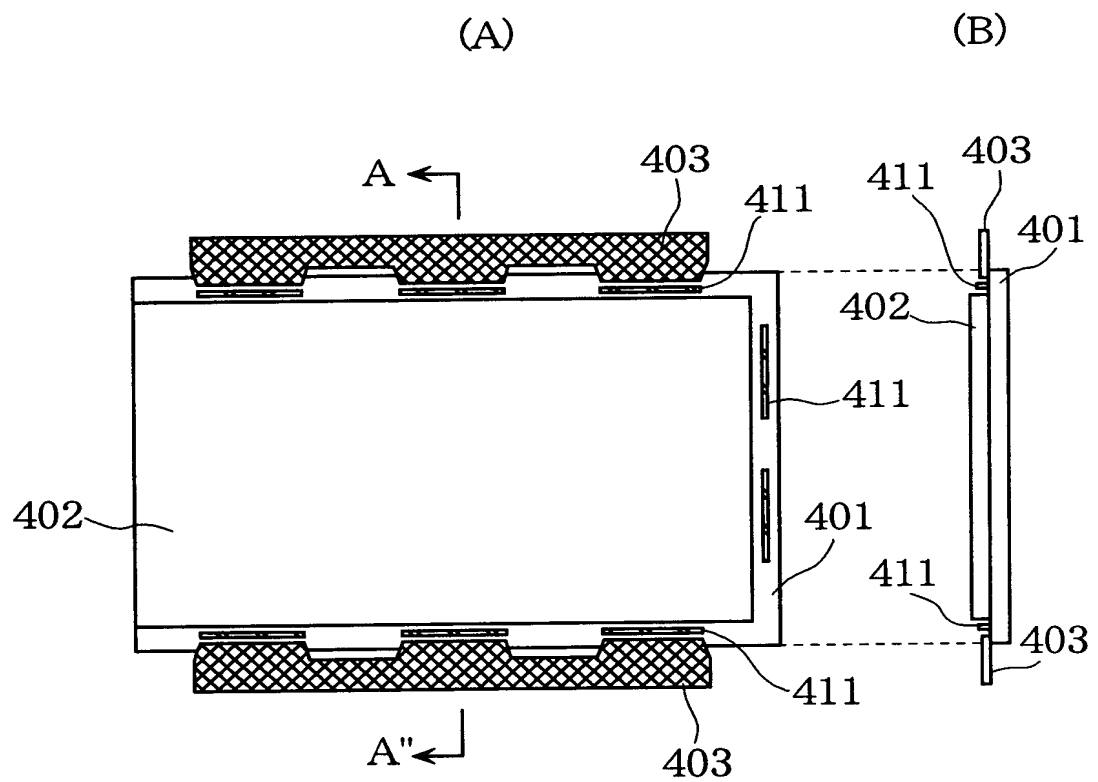


Fig. 37

